

What is claimed is:

1. A multi-layer electrode for an integrated circuit,
comprising:
 - a conductive barrier layer;
 - 5 a first conductive liner deposited over the
conductive barrier layer;
 - a second conductive liner deposited over the first
conductive liner; and
 - a conductive layer deposited over the second
- 10 conductive liner, wherein the conductive layer and the
first conductive liner comprise the same material.
2. The multi-layer electrode according to Claim 1
wherein the second conductive liner comprises a
- 15 conductive oxide.
3. The multi-layer electrode according to Claim 2
wherein the second conductive liner is 20-50 Angstroms
thick.
- 20 4. The multi-layer electrode according to Claim 3
wherein the conductive layer and the first conductive
liner comprise Pt.
- 25 5. The multi-layer electrode according to Claim 4
wherein the first conductive liner is 200-500 Angstroms
thick.
- 30 6. The multi-layer electrode according to Claim 5
wherein the conductive barrier layer comprises TaSiN.
7. The multi-layer electrode according to Claim 6
wherein the integrated circuit comprises a DRAM or an
- 35 FRAM.

8. A multi-layer electrode for an integrated circuit,
comprising:

a conductive barrier layer;

5 a first conductive liner deposited over the
conductive barrier layer;

a second conductive liner deposited over the first
conductive liner, the second conductive liner comprising
a conductive oxide; and

10 a conductive layer deposited on the second
conductive liner.

9. The multi-layer electrode according to Claim 8
wherein the second conductive liner is 20-50 Angstroms
thick.

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10. The multi-layer electrode according to Claim 8
wherein the conductive layer and the first conductive
liner comprise Pt.

20 11. The multi-layer electrode according to Claim 8
wherein the first conductive liner is 200-500 Angstroms
thick.

25 12. The multi-layer electrode according to Claim 8
wherein the conductive barrier layer comprises TaSiN.

13. The multi-layer electrode according to Claim 8
wherein the integrated circuit comprises a DRAM or an
FRAM.

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14. A method of fabricating an electrode of an integrated circuit, comprising:

depositing a conductive barrier layer over a substrate;

5 depositing a first conductive liner over the conductive barrier layer;

depositing a second conductive liner over the first conductive liner; and

10 depositing a conductive layer over the second conductive liner, wherein the conductive layer and the first conductive liner comprise the same material.

15 15. The method according the Claim 14 wherein depositing a second conductive liner comprises depositing a conductive oxide.

20 16. The method according to Claim 15 wherein depositing the second conductive liner comprises depositing 20-50 Angstroms of the conductive oxide.

17. The method according to Claim 16 wherein depositing a conductive layer and depositing a first conductive liner comprise depositing Pt.

25 18. The method according to Claim 17 wherein depositing the first conductive liner comprises depositing 200-500 Angstroms of Pt.

30 19. The method according to Claim 18 wherein depositing a conductive barrier layer comprises depositing TaSiN.

20. The method according to Claim 19 wherein the integrated circuit comprises a DRAM or an FRAM.